

RECEIVED
CENTRAL FAX CENTER
JUN 24 2008

In re the Application of: **HORIE, Tsutomu**

Group Art Unit: **2886**

Serial No.: **10/709,244**

Examiner: **Isiaka Akanbi**

Filed: **April 23, 2004**

P.T.O. Confirmation No.: **3243**

For: **RETICLE, RETICLE INSPECTION METHOD AND RETICLE INSPECTION
APPARATUS**

RESPONSE and PETITION FOR EXTENSION OF TIME

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Docket **040186**

June 24, 2008

Sir:

In response to the Office Action dated January 29, 2008, extended to June 29, 2008, by a two-month Petition for Extension of Time, this paper is a petition for an appropriate extension of time. Please charge any fees needed for such an extension of time, and any other fees which may be due with respect to this paper, to **Deposit Account No. 01-2340**.

REMARKS

The Applicant provides a device pattern in the exposure area and an intentionally defective evaluation pattern in an area outside the exposure area. The evaluation patterns correspond to different types of defects that can occur in the exposure area, and are arranged by the type of defect.